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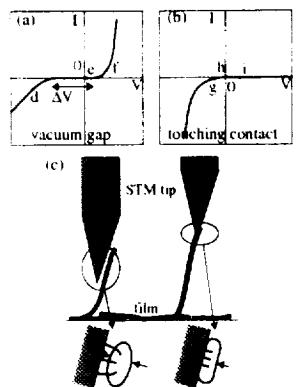
I-V characteristics of STM tip-nanotube characteristics

Analysis of Long-channel Nanotube FETs

Toshishige Yamada

NASA Ames Research Center

vacuum gap mode vs. touching mode

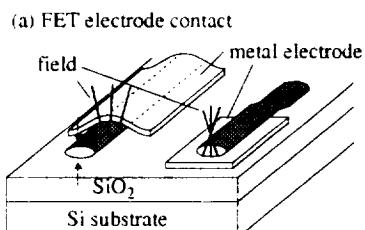


conduction/valence
band tunneling

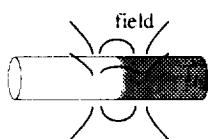
Schottky forward/reverse
transport

nanotube FET contact

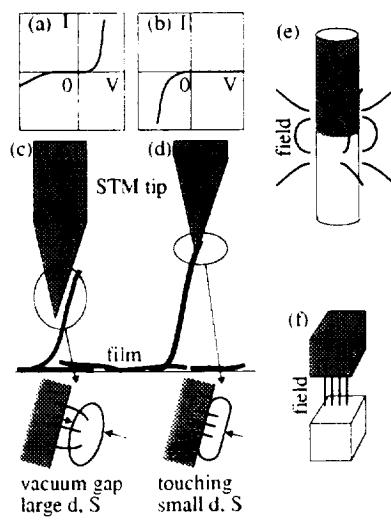
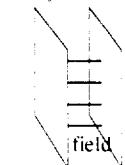
low T room T
vacuum gap mode vs. touching mode

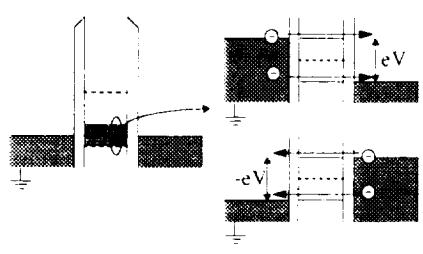
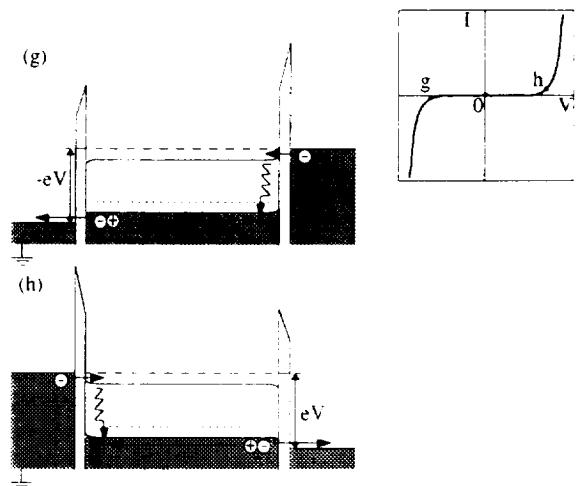
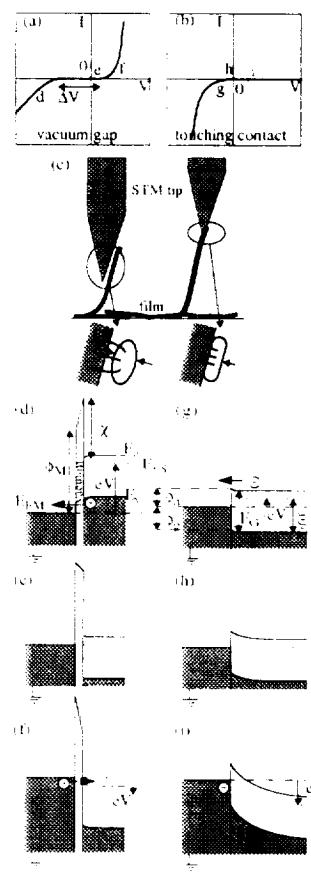
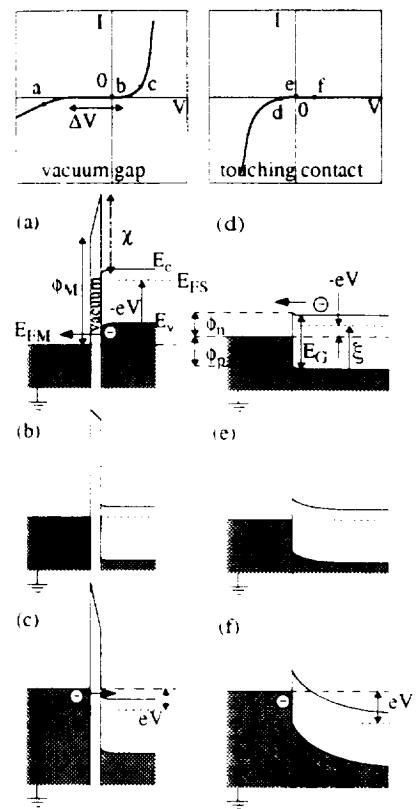
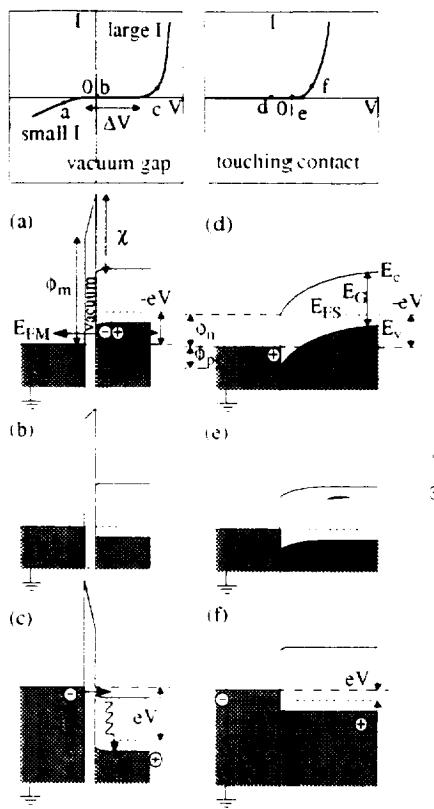


(b) 1D junction

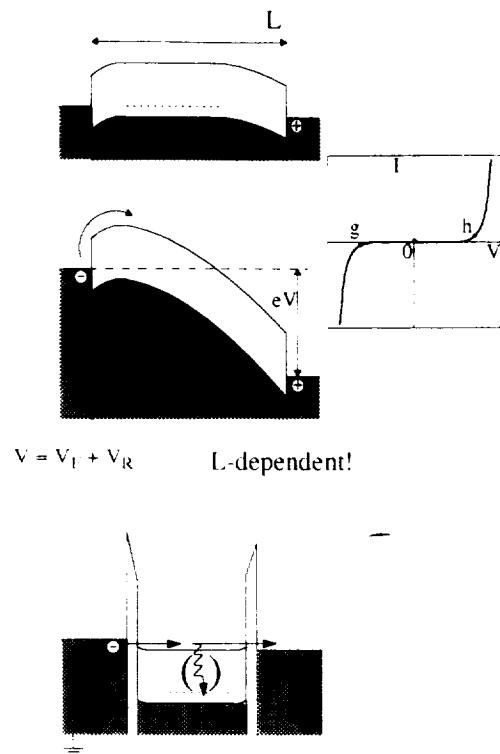


(c) planar junction

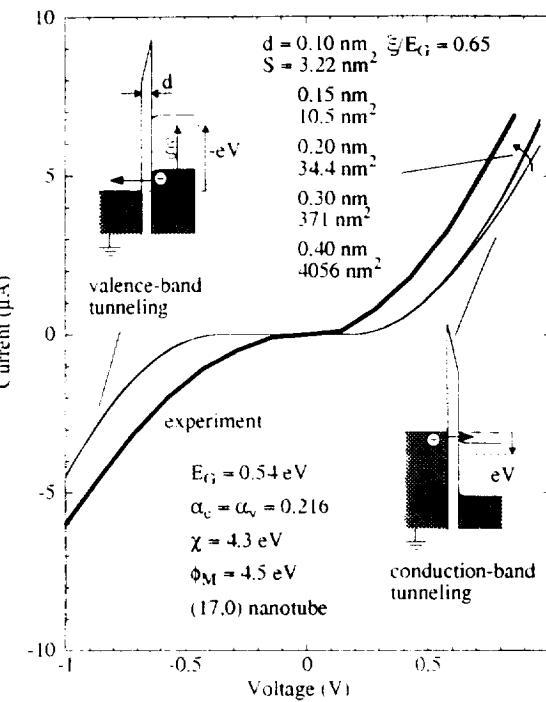




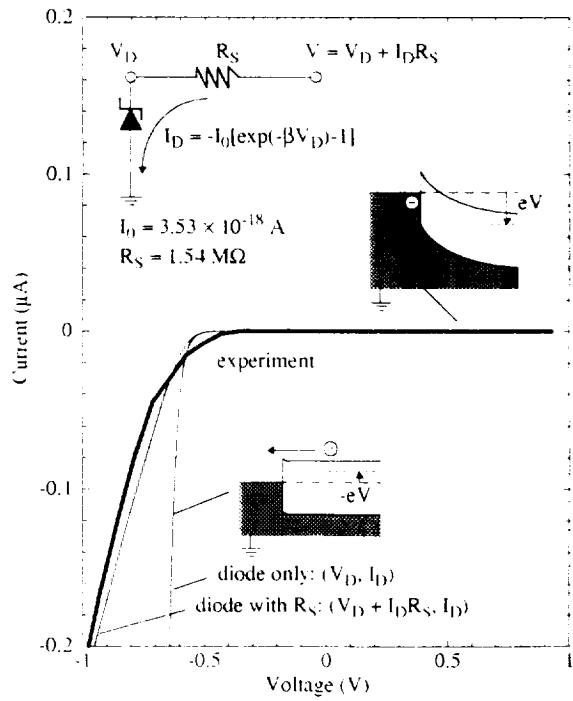
Reach-through



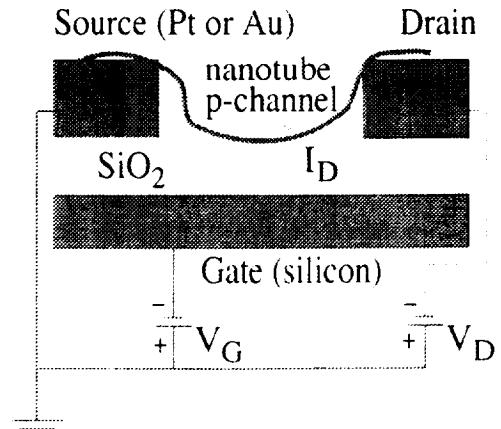
this is like a saturation mode in BJT. without V_g this will never happen for a two-terminal device



Nanotube FET by Delft, IBM



[Delft] S.J. Tans, A.R.M. Verschueren, and C. Dekker, Nature **393**, 49 (98)
 [IBM] R. Martel, T. Schmidt, H.R. Shea, T. Hertel, and Ph. Avouris, Appl. Phys. Lett. **73**, 2447 (98)



measure

$I_D(V_D)$ at fixed V_G

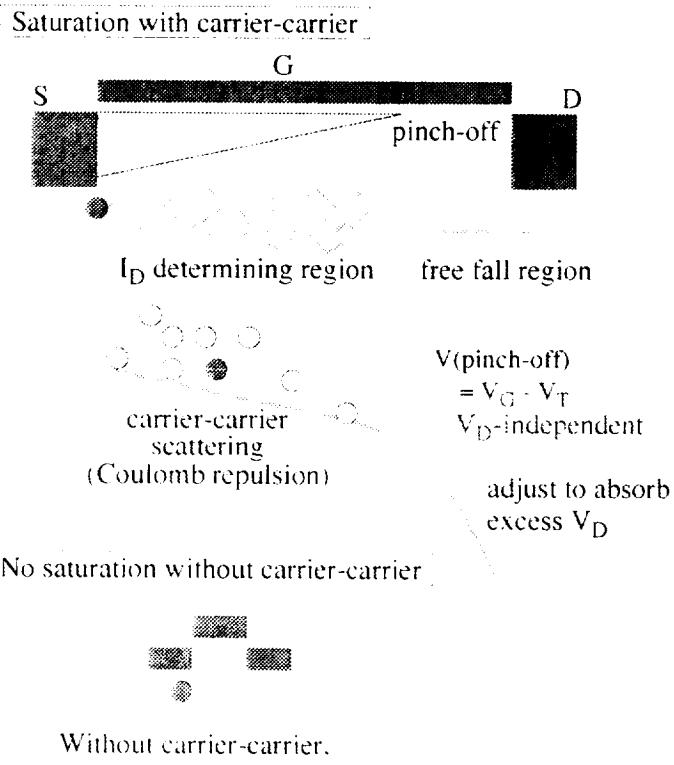
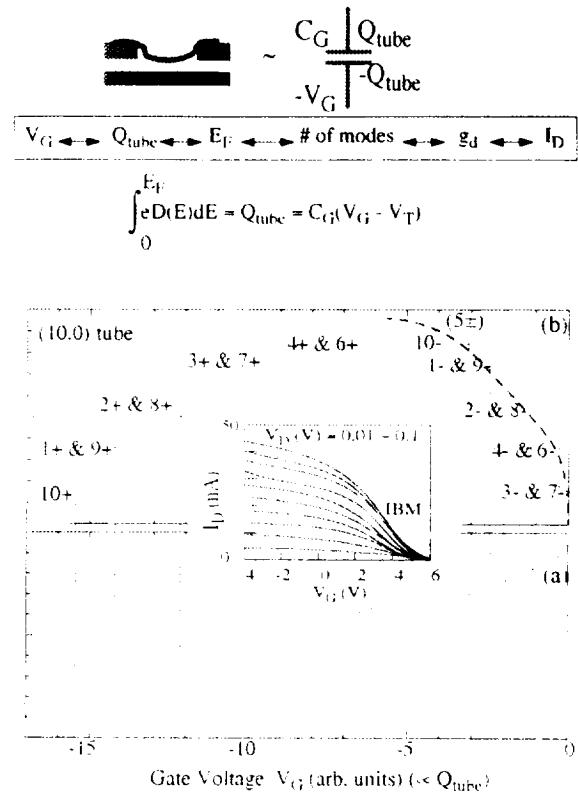
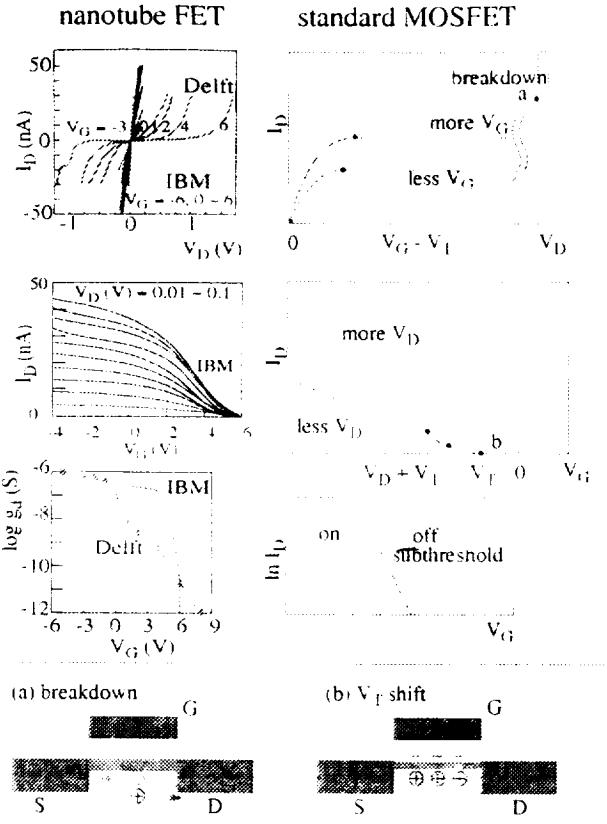
$I_D(V_G)$ at fixed V_D

channel conductance

$g_d = \partial I_D / \partial V_D$

transconductance

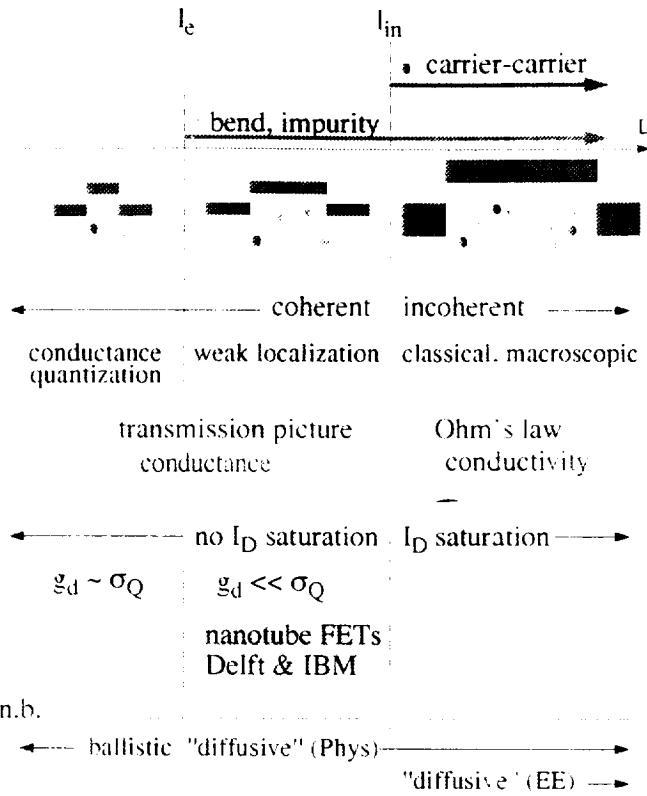
$g_m = \partial I_D / \partial V_G$



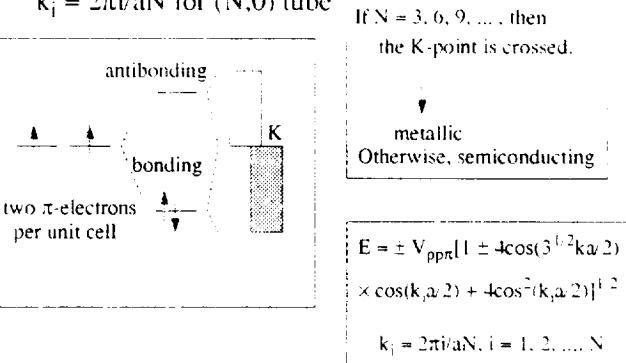
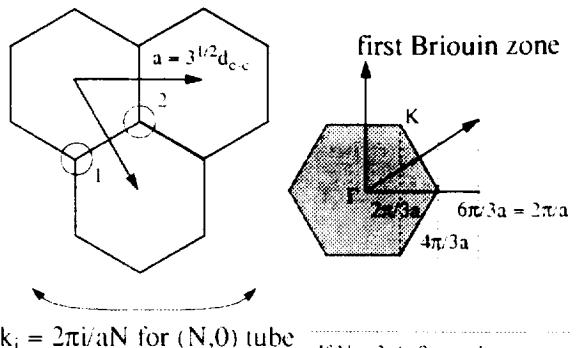
Experimental observations & possible mechanisms:

1. saturationless $I_D(V_D)$ fixing V_G of Delft
absence of carrier-carrier scattering
a lot of elastic scattering, low g_d
2. breakdown in $I_D(V_D)$ fixing V_G of Delft
usual pair creation
3. kink in subthreshold $g_d(V_G)$ of Delft (Pt S & D)
4. smooth subthreshold $g_d(V_G)$ of IBM (Au S & D)
Schottky barrier effects
5. saturated "on" $I_D(V_G)$ fixing V_D of IBM
quasi-1D nanotube characteristics
6. large V_G shift in $g_d(V_G)$ of Delft, IBM
usual Q_{int} effects

Gate length L , elastic length l_e , & inelastic length l_{in}



Electronic properties of carbon nanotube

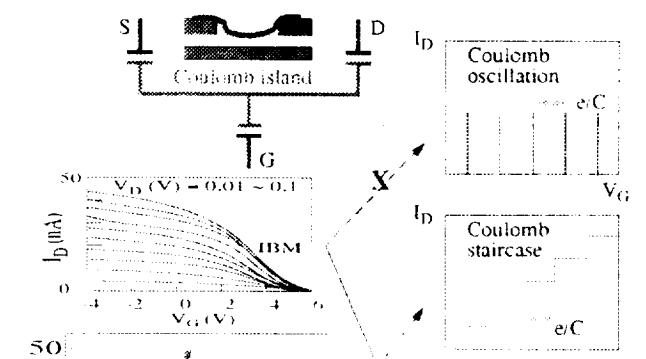


$$E = \pm V_{ppr} [1 \pm 4\cos(3^{1/2}ka/2) \times \cos(k_x a/2) + 4\cos^2(k_x a/2)]^{1/2}$$

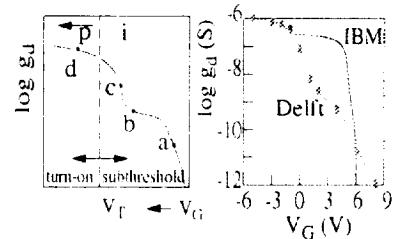
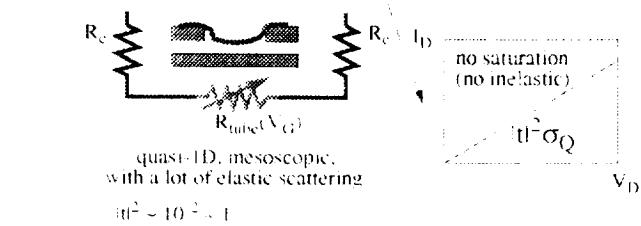
$$k_i = 2\pi i/aN, i = 1, 2, \dots, N$$

Theoretical nanotube FET characteristics

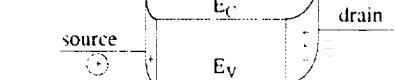
isolating contact



penetrating contact



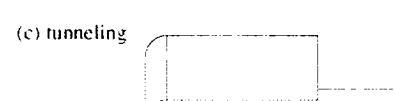
turn-on, subthreshold



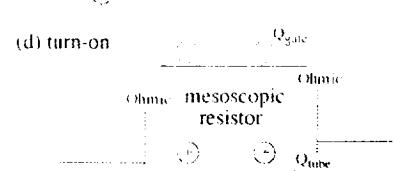
source drain



source drain



source drain



source drain